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Attorney Docket No.: 101328-180

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Karen K. Gleason et al.

Application No.: 10/624,959 – 6293

Group Art Unit: Not Yet Assigned

Filed: July 22, 2003

Examiner: Not Yet Assigned

For: Porous Material Formation By Chemical Vapor
Deposition Onto Colloidal Crystal Templates

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

TRANSMITTAL LETTER

Dear Sir:

I enclose herewith for filing in the above-identified application the following:

1. Information Disclosure Statement;
2. PTO/SB/08 Form cited (46) references thereon;
3. Copies of each Foreign Patent and Non-Patent Reference cited; and
4. Return receipt postcard.

The Commissioner is authorized to charge any overpayments or underpayments if necessary to our Deposit Account No. 141449, Reference No. 101328-180, Customer No. 021125. A duplicate of this sheet is enclosed.

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June 23, 2004

Date

Deborah A. Miller, Reg. No 53,328

Respectfully submitted,

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Agent For Applicants

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June 23, 2004
Date of Signature and of Mail Deposit

By:

Deborah A. Miller
Deborah A. Miller, Reg. No. 53,328
Agent for Applicants

Commissioner for Patents
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INFORMATION DISCLOSURE STATEMENT

Dear Sirs:

Pursuant to 37 C.F.R. §1.56, §1.97 and §1.98, Applicant herewith makes of record the enclosed documents listed on the attached copy of PTO/SB/08A. In accordance with §1.97(b), this Information Disclosure Statement is being filed prior to the mailing date of a first Office Action on the merits.

Applicants have not submitted copies of each cited U.S. patent and each U.S. patent application as required by 37 C.F.R. 1.98 (a)(2)(i) since the U.S. Patent and Trademark Office has waived this requirement for all U.S. patent applications filed after June 30, 2003. If a copy of any cited reference is needed, please call the undersigned at the telephone number indicated below.

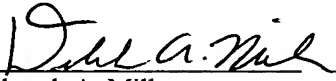
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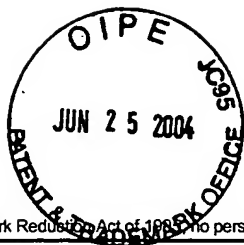
make an independent evaluation of the cited publications.

No fee is believed to be due in connection with the filing of this paper. However, if any fee is due, the Commissioner is hereby authorized to charge payment of any additional fees associated with this communication or credit any overpayment to Deposit Account No. 141449.

Dated: June 23, 2004

Respectfully submitted,

By 
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PTO/SB/08A (10-01)

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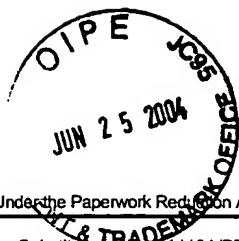
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Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Complete if Known	
				Application Number	10/624,959 (Conf #6293)
				Filing Date	July 22, 2003
				First Named Inventor	Karen K. Gleason
				Art Unit	Not Yet Assigned
				Examiner Name	Not Yet Assigned
Sheet	1	of	3	Attorney Docket Number	101328-180

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
	AA	4,599,243	07/08/1986	Sachdev et al.	
	AB	5,521,126	05/28/1996	Okamura et al.	
	AC	6,068,884	05/30/2000	Rose et al.	
	AD	6,090,724	07/18/2000	Shelton et al.	
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	AT	2002/0137359 A1	09/26/2002	Grill et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country-Number				
	BA	EP 1 321 976 A2	06/25/2003	Canon Sales Co., Inc.		
	BB	EP 1 148 539 A2	10/24/2001	Applied Materials, Inc.		
	BC	EP 1 195 451 A1	04/10/2002	Applied Materials, Inc.		
	BD	WO 03/005429 A1	01/16/2003	Postech Foundation		



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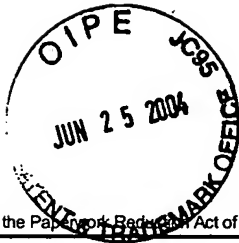
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Sheet	2	of	3	Attorney Docket Number	101328-180

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²	
	CA	Baklanov, M.R. et al. "Comparative Study of Porous SOG Films With Different Non-Destructive Instrumentation," IEEE pp. 189-191, (2001);		
	CB	Barklanov, M.R. "Determination of Pore Size Distribution In Thin Films By Ellipsometric Porosimetry" J. Vac. Sci. Technol. B., Vol. 18, No. 3, pp. 1385-13981, (2000);		
	CC	Baklanov, M.R., Mogilnikov, K.P., "Non-Destructive Characterisation of Porous Low-K Dielectric Films," Microelectronic Engineering, Vol. 64, pp. 335-349, (2002);		
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	CF	Grill, A. and Patel, V. "Ultralow-k Dielectrics Prepared By Plasma-Enhanced Chemical Vapor Deposition," Applied Physics Letters, Vol. 79, No. 6, pp. 803-805 (2001);		
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	CK	Hedrick, J. L. et al. "Templating Nanoporosity In Thin-Film Dielectric Insulators," Adv. Mater. Vol. 10, No. 13 pp. 1049-1053 (1998);		
	CL	Park, S.H. and Xia, Y. "Macroporous Membranes With Highly Ordered And Three-Dimensionally Interconnected Spherical Pores," Advanced Materials, Vol. 10, No. 13, pp. 1045-1053 (1998);		
	CM	Peters, L. "Low-K Dielectrics: Will Spin-On or CVD Prevail?," Semiconductor international, pp. 108-124, (2000);		
	CN	Peters, L. "Removing Barriers To Low-K Dielectric Adoption," Semiconductor International 53-62, (2002);		
	CO	Sanchez, M.I. et al. "Nanofoam Porosity By Infrared Spectroscopy," Journal of Polymer Science: Part B: Polymer Physics, Vol. 33, pp. 253-257 (1995);		
	CP	Sanchez, M.I. et al. "Nanofoam Porosity Measured By Infrared Spectroscopy And Refractive Index," Mat. Res. Soc. Symp. Proc., Vol. 431, pp. 475-480, (1996);		
	CQ	Vrtis, R.N. et al. "Plasma Enhanced Chemical Vapor Deposition of Porous Organosilicate Glass ILD Films With k ≤ 2.4," Mat. Res. Soc. Symp. Proc., Vol. 766, pp. E7.4.1-E7.4.6, (2003);		
	CR	Wu, Q. and Geason, K.K. "Plasma-Enhanced Chemical Vapor Deposition of Low-k Dielectric Films Using Methylsilane, Dimethylsilane, and Trimethylsilane Precursors," J. Vac. Sci. Technol., Vol. A 21, No. 2, pp. 388-393 (2003);		
	CS	Yang, S. et al. "Nanoporous Ultralow Dielectric Constant Organosilicates Templated By Triblock Copolymers," Chem. Mater., Vol. 14, pp. 369-374 (2002);		



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	CT	Yim, J-H. et al. "The Preparation and Characterization of Small Mesopores In Siloxane-Based Materials That Use Cyclodextrins as Templates," Adv. Funct. Mater., Vol. 13, No. 5, pp. 382-386 (2003);	
	CU	Ye, Y-H. et al. "Large-Scale Ordered Macroporous SiO ₂ Thin Films by a Template-Directed Method," Applied Physics Letters, Vol. 81, No. 4, pp. 616-618, (2002);	
	CV	Zhang, P. et al. "Theory of Metastable Group-IV Alloys Formed From CVD Precursors," Physical Review B, Vol. 64, pp. 235201-1- 235201-10 (2001).	
Examiner Signature			Date Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Applicant's unique citation designation number (optional). ²Applicant is to place a check mark here if English language Translation is attached.

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